Replace from the paragraph beginning at page 2, line 24 to the paragraph ending at page 7, line 17, with the following rewritten paragraph/s:

Moreover, Japanese Unexamined Patent Publication JP-A 9-90426 (1997) discloses a technology to simultaneously expose an asperity forming pattern and contact holes using only one layer of a photosensitive resin in order to reduce the process of manufacturing a reflective-type liquid crystal display apparatus.

A method of manufacturing a reflective-type liquid crystal display apparatus described in this patent publication will briefly be described with reference to the drawings. In this regard, Fig. 22 illustrates a mask used in this reference (JP 9-90426).

In the reflective-type liquid crystal display apparatus described in the above-mentioned patent publication, the following are provided: an aluminum pixel electrode disposed on the reflecting substrate; a transparent electrode opposed thereto; a color filter substrate supporting the transparent electrode; liquid crystal sandwiched therebetween; and a polarizing plate 116 disposed above the phase difference plate 115.

A method of manufacturing the reflecting substrate of the reflective-type liquid crystal display apparatus described in the above-mentioned patent publication will be described.

First, a photosensitive resin is applied to the substrate.

Then, exposure is carried out using the photomask shown in Fig. 22 having a large light-blocking contact hole portion and in addition thereto, a plurality of smaller light blocking portions at asperity forming portions